-	161	(h01l021\$.ipc. c23c016\$.ipc.) and ((electrode cathode anode)	JPO;	2003/06/28 23:05
		with (curve curves curvature curving nonplanar concave convex))	DERWENT	
		and ((ceramic alumina dielectric insulate insulated insulating		
		insulates insulation) with (curve curves curvature curving		
	538	nonplanar concave convex)) (156/345.43; 156/345.44; 156/345.45; 156/345.46;	USPAT	2004/01/13 08:05
-	538	(156/345.45; 156/345.44; 156/345.45; 156/345.46;   156/345.47).CCLS.	USPAT	2004/01/13 08:05
_	978	(118/723e).CCLS.	USPAT	2004/01/13 08:07
	1292	((156/345.43; 156/345.44; 156/345.45; 156/345.46;	USPAT	2004/01/13 08:07
	1232	156/345.47).CCLS.) ((118/723e).CCLS.)	03/7/1	2001/01/15 00.07
-	48	(((156/345.43; 156/345.44; 156/345.45; 156/345.46;	USPAT	2004/01/13 08:10
		156/345.47).CCLS.) ((118/723e).CCLS.)) not @pd<=20030601		
	1	("5702562").PN.	USPAT	2004/01/13 09:40
-	10	(("6178919") or ("6129806") or ("6165376") or ("0594713") or	USPAT	2004/01/13 10:00
		("5300460") or ("6171438") or ("5942075") or ("5772833") or		
		("5779849") or ("6110287")).PN.		
-	219041	(wafer substrate work object) with (size diameter)	USPAT	2004/01/13 10:01
-	431	((wafer substrate work object) with (size diameter)) and	USPAT	2004/01/13 10:01
	262	118/723e.ccls.	LICDAT	2004/01/12 10:02
-	263	((wafer substrate work object) with (size diameter)) and 118/723r.ccls.	USPAT	2004/01/13 10:02
-	67	((wafer substrate work object) with (size diameter)) and	USPAT	2004/01/13 10:02
	0,	156/345.43.ccls.	33171	200 1/01/13 10.02
_	69	((wafer substrate work object) with (size diameter)) and	USPAT	2004/01/13 10:02
		156/345.46.ccls.		,
-	- 22	((wafer substrate work object) with (size diameter)) and	USPAT	2004/01/13 10:02
		156/345.45.ccls.		
-	38	((wafer substrate work object) with (size diameter)) and	USPAT	2004/01/13 10:02
	مَم	156/345.44.ccls.		55545445445
-	89	((wafer substrate work object) with (size diameter)) and	USPAT	2004/01/13 11:29
	7807	156/345.47.ccls.	LICDAT	2004/01/13 11:30
_	1076	large adj2 display\$ (large adj2 display\$) and (large with (substrate wafer))	USPAT USPAT	2004/01/13 11:30
_	688	(156/345.43; 156/345.44; 156/345.45; 156/345.46;	USPAT;	2004/01/13 11:34
	000	156/345.47).CCLS.	US-PGPUB	2004/01/13 11.31
  -	1166	(118/723e).CCLS.	USPAT;	2004/01/13 11:32
İ			US-PGPUB	
-	538	(156/345.43; 156/345.44; 156/345.45; 156/345.46;	USPAT	2004/01/13 11:31
		156/345.47).CCLS.		*
_	978	(118/723e).CCLS.	USPAT	2004/01/13 11:32
	1 1000	("0000067").PN.	USPAT	2004/01/13 11:32
	1292	((156/345.43; 156/345.44; 156/345.45; 156/345.46; 156/345.47).CCLS.) ((118/723e).CCLS.)	USPAT	2004/01/13 11:32
_	1	156/345.47).CCLS.) ((118/7238).CCLS.)   (((156/345.43; 156/345.44; 156/345.45; 156/345.46;	USPAT	2004/01/13 11:33
	1	(((130/343.43, 130/343.44, 130/343.43, 130/343.46,   156/345.47).CCLS.) ((118/723e).CCLS.)) and (large adj2 display\$)	ODEA1	CC.11 C1/110/L002
_	. 1	(((156/345.43; 156/345.44; 156/345.45; 156/345.46;	USPAT	2004/01/13 11:33
ı	_	156/345.47).CCLS.) ((118/723e).CCLS.)) and ((large adj2		
		display\$) and (large with (substrate wafer)))		
-	4746	118/723\$.ccls. 156/345\$.ccls.	USPAT	2004/01/13 11:34
-	10	(118/723\$.ccls. 156/345\$.ccls.) and (large adj2 display\$)	USPAT	2004/01/13 11:37
-	1512	(118/723\$.ccls. 156/345\$.ccls.) and (large with (substrate wafer))	USPAT	2004/01/13 11:38
÷	574	(118/723\$.ccls. 156/345\$.ccls.) and (large adj2 (substrate wafer))	USPAT	2004/01/13 12:22
-	445	((118/723\$.ccls. 156/345\$.ccls.) and (large adj2 (substrate	USPAT	2004/01/13 11:39
_	755417	wafer))) and (cathode anode electrode) h01l021\$.ipc. c23c0156\$.ipc. and (large adj2 (substrate wafer))	JPO;	2004/01/12 12:02
- 	/2241/	notiozta.ipc. czacotaoa.ipc. and (large adjz (substrate water))	DERWENT	2004/01/13 12:07
-	755417	h01l021\$.ipc. c23c0156\$.ipc.	JPO;	2004/01/13 12:07
	, 33117	TO LOCAL PRINCIPOLITICAL PRINC	.DERWENT	200 1, 01, 13 12.07
-	1867	(h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate wafer))	JPO;	2004/01/13 12:07
		, , , , , , , , , , , , , , , , , , , ,	DERWENT	, , , , , , , , , , , , , , , , , , , ,
-	0	(((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO;	2004/01/13 12:08
	.= . =	wafer))) and (cathode anode electrode)) and (large adj2 display\$)	DERWENT	
_	312	((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO;	2004/01/13 12:13
		wafer))) and (cathode anode electrode)	DERWENT	

-	5	(((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO	2004/01/13 13:05
		wafer))) and (cathode anode electrode)) and (meter\$ inch\$2)		2024/24/42 42 42
-	54	(((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO	2004/01/13 12:16
		wafer))) and (cathode anode electrode)) and (m in)	LIGDAT	2004/04/42 42 22
· ·	544	((118/723\$.ccls. 156/345\$.ccls.) and (large adj2 (substrate	USPAT	2004/01/13 12:23
		wafer))) and ((wafer substrate) with ("m" "in"))	LICDAT	2004/01/12 12-21
-	348	((118/723\$.ccls. 156/345\$.ccls.) and (large adj2 (substrate	USPAT	2004/01/13 12:31
		wafer))) and ((wafer substrate) near4 ("m" "in"))	LICDAT	2004/01/12 12:24
-	74	((118/723\$.ccls. 156/345\$.ccls.) and (large adj2 (substrate	USPAT	2004/01/13 12:24
		wafer))) and ((wafer substrate) near ("m" "in"))	100	2004/01/13 12:33
-	19	((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO	2004/01/13 12.33
		wafer))) and (meter\$ inch\$2)	JPO	2004/01/13 12:36
-	14	(((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO	2004/01/13 12.30
		wafer))) and (meter\$ inch\$2)) not ((((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate wafer))) and (cathode		
		anode electrode)) and (meter\$ inch\$2))		
	2020		USPAT	2004/01/13 12:37
_	2829	"applied materials".as. "applied materials".as. and (large adj2 display\$)	USPAT	2004/01/13 12:39
_	255	"applied materials".as. and (large adj2 displays)  "applied materials".as. and (large adj2 (substrate\$ wafer\$))	USPAT	2004/01/13 12:59
-	255	("applied materials".as. and (large adj2 (substrate\$ water\$))) and	USPAT	2004/01/13 13:05
] -		("m.sup.2" "in.sup.2")	55.7.1	
	26	("4184188"   "4298443"   "4384918"   "4431473"   "4931135"	USPAT	2004/01/13 13:01
- 00	20	"5092729"   "5179498"   "5304249"   "5310453"   "5366585"		
		"5399387"   "5413360"   "5458687"   "5531835"   "5547539"		
		"5558717"   "5790365"   "5874361"   "5897711"   "5900062"		
		"5904779"   "5906684"   "5910338"   "6001432"   "6028762"		
		"6177023").PN.		
_	18	("4184188"   "4298443"   "4384918"   "4431473"   "4931135"	USPAT	2004/01/13 13:04
		"5092729"   "5179498"   "5304249"   "5310453"   "5458687"		
		"5547539"   "5790365"   "5897711"   "5900062"   "5904779"		
8		"5906684"   "5910338"   "6001432").PN.		
- ,	0	(((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO;	2004/01/13 13:06
,		wafer))) and (cathode anode electrode)) and ("m.sup.2"	DERWENT	
		"in.sup.2")		0004/04/12 42 00
-	Ò	((h01l021\$.ipc. c23c0156\$.ipc.) and (large adj2 (substrate	JPO;	2004/01/13 13:06
		wafer))) and ("m.sup.2" "in.sup.2")	DERWENT	2004/01/12 12:06
-	0	(h01l021\$.ipc. c23c0156\$.ipc.) and ("m.sup.2" "in.sup.2")	JPO;	2004/01/13 13:06
		//// 10/700#!- 150/245# ada \ //a adi? /abab	DERWENT	2004/01/13 13:15
-	21	((((118/723\$.ccls. 156/345\$.ccls.) and (large adj2 (substrate	USPAT	2007/01/13 13.13
		wafer))) and ((wafer substrate) with ("m" "in"))) and ("m.sup.2"		
		"in.sup.2")	DERWENT	2004/01/13 13:18
] <del>-</del>	1	("5981899").PN. 1998-414355.NRAN.	DERWENT	2004/01/13 13:16
<u> </u>	1	("6177023").PN.	DERWENT	2004/01/13 13:20
	1 1	1999-250789.NRAN.	DERWENT	2004/01/13 13:18
	1	("6298685").PN.	DERWENT	2004/01/13 13:21
_	1	2001-612327.NRAN.	DERWENT	2004/01/13 13:20
-	2	(("5942075") or ("6178919")).PN.	DERWENT	2004/01/13 13:23
-	1	2000-611214.NRAN.	DERWENT	2004/01/13 13:21
_	1		DERWENT	2004/01/13 13:22
	3	(("5942075") or ("6178919") or ("5237152")).PN.	USPAT	2004/01/13 14:47
-	2	(("5272417") or ("5210466")).PN.	USPAT	2004/01/13 14:52
-	1	1 22	USPAT	2004/01/13 14:52